



D. Thin Film Process Technology 분과

2021년 1월 25일(월), 10:45-12:15 / 채널 A

[MA2-D] Ferroelectric Films II

좌장: 김성근 박사 (KIST), 이웅규 교수 (명지대학교)

<p>MA2-D-1 10:45-11:00</p>	<p>Pulsed I-V Method for Characterizations on Genuine Ferroelectric Field Effects of the MFMIS-FETs Using Hf-Zr-O Gate Insulators</p> <p>Tae-Hyun Ryu, Dae-Hong Min, and Sung-Min Yoon <i>Department of Advanced Materials Engineering for Information and Electronics, Kyung Hee University</i></p>
<p>MA2-D-2 11:00-11:15</p>	<p>철회</p>
<p>MA2-D-3 11:15-11:30</p>	<p>Defect Engineering을 통한 TiN/H_{0.5}Zr_{0.5}O₂/TiN 커패시터의 Wake-up Effect와 강유전성 개선</p> <p>Hyungwoo Kim^{1,2}, Alireza Kashir^{1,2}, Seungyeol Oh^{1,2}, and Hyunsang Hwang^{1,2} ¹<i>Center for Single Atom-based Semiconductor Device, POSTECH,</i> ²<i>Department of Materials Science and Engineering, POSTECH</i></p>
<p>MA2-D-4 11:30-11:45</p>	<p>Seed Layer Effect of HZO Nanolaminate Structure on Tungsten Electrode</p> <p>Seung-Min Han^{1,2}, Dae-Hwan Ahn¹, Woo-Young Choi², and Jae-Hoon Han¹ ¹<i>Center for Opto-Electronic Materials and Devices, KIST,</i> ²<i>Department of Electrical and Electronic Engineering, Yonsei University</i></p>
<p>MA2-D-5 11:45-12:00</p>	<p>Laser Drilling Via Process for 3-D Flexible Integrated Circuits</p> <p>Suwon Seong, Seongmin Park, Jueun Kim, and Yoonyoung Chung <i>Department of Electrical Engineering, POSTECH</i></p>
<p>MA2-D-6 12:00-12:15</p>	<p>Study of Ferroelectric Characteristics of Hf_{0.5}Zr_{0.5}O₂ Thin Films Grown on Sputtered or Atomic-layer Deposited TiN Bottom Electrodes</p> <p>Beom Yong Kim^{1,2,3}, Hyeon Woo Park^{1,2}, Seung Dam Hyun^{1,2}, Yong Bin Lee^{1,2}, Suk Hyun Lee^{1,2}, Minsik Oh^{1,2}, Seung Kyu Ryu^{1,2}, In Soo Lee^{1,2}, Seung Yong Byun^{1,2}, Soo Jin Jo^{1,2}, Do Sup Shim^{1,2}, and Cheol Seong Hwang^{1,2} ¹<i>Department of Materials Science and Engineering, Seoul National University,</i> ²<i>Inter-University Semiconductor Research Center, Seoul National University,</i> ³<i>R&D Division, SK Hynix Inc.</i></p>